

**Amendments to the Claims**

41. (Currently amended) A transistor structure, comprising:

a gate oxide layer on a semiconductive substrate, , 5X; the gate oxide layer

having a nitrogen-enriched region which is only in an upper half of the gate oxide layer;

a conductive layer on the gate oxide layer; and

source/drain regions within the semiconductive substrate; the source/drain regions being gatedly connected to one another by the conductive layer.

42. (Original) The structure of claim 41 wherein the conductive layer comprises conductively-doped silicon.

43. (Original) The structure of claim 41 wherein the conductive layer comprises p-type conductively-doped silicon.